ANTIFUSE STRUCTURE AND METHOD FOR MANUFACTURING IT

ABSTRACT

An improved antifuse design has been achieved by providing a structure comprising pair of alternating layers of silicon nitride and amorphous silicon sandwiched between two dual damascene connectors. Said structure provides the advantage, over the prior art, that all electrically active surfaces of the fuse structure are planar, so no potential failure spots resulting from surface unevenness can be formed. A process for manufacturing said fuse structure is also provided and involves fewer masking steps than related structures of the prior art.

(FIGURE 2 IS SUGGESTED FOR PUBLICATION)